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PATENT ABSTRACTS OF JAPAN

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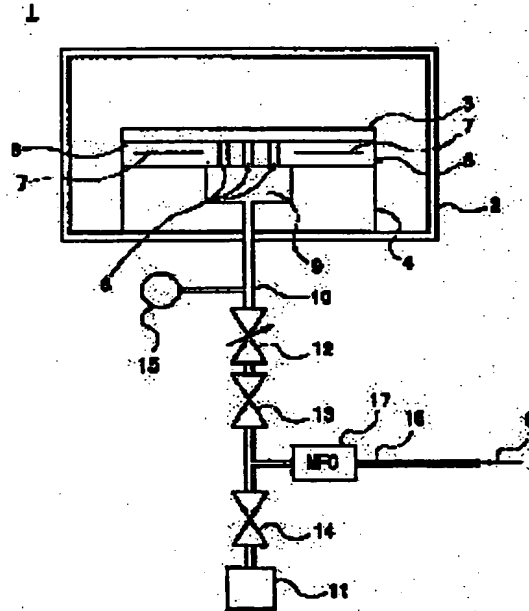
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(54) METHOD FOR MONITORING ATTRACTION STATE OF ATTRACTED OBJECT, AND VACUUM DEVICE THEREOF

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for monitoring the attraction state of an attracted object for easily and positively detecting the presence or absence of failure in the attraction of the attracted object in all processes, regardless of process conditions and the type of electrostatic chuck, and a vacuum device.

SOLUTION: A substrate 3 is attracted and retained by an electrostatic chuck 5. After that, a gas G for monitoring is supplied by a gas-introducing pipe 16, and a pipe 10 and the gas G is introduced into the gap between the substrate 3 and an electrostatic chuck plate 6 via a gas inlet port 8 of the electrostatic chuck plate 6 from an accommodation part 9 of a susceptor 4. In this state, the change in the pressure of the gap between the substrate 3 and the electrostatic chuck plate 6 is measured by a vacuum meter 15, thus easily discriminating whether the substrate 3 is attracted normally and retained with respect to the electrostatic chuck 5.



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